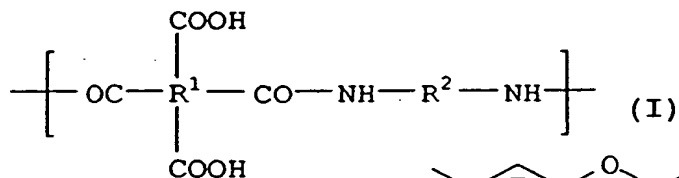


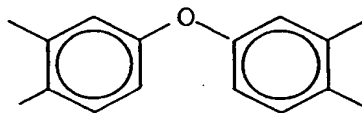
Abstract:

There are disclosed a photosensitive resin composition which comprises

(A) a polyamic acid having recurring units represented by the formula (I):



wherein R^1 represents



; and R^2

represents a divalent organic group, and

(B) an acryl compound having an amino group,

and also a photosensitive resin composition for an i-line stepper which further comprises a photoinitiator in addition to the photosensitive resin composition.